

L Number	Hits	Search Text	DB	Time stamp
1	3461	(SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:00
8	4556	(250/306,307,311,442.11)).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 15:59
15	839	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:00
22	123	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:01
29	77	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:01
36	72	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:01
43	23	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:02
50	22	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:03
57	19	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:06
64	19	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:06
71	19	((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:07

78	14	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:09
85	12	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:10
92	12	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:11
99	1	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and arithmetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:11
106	12	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:12
113	12	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:12

120	12	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:12
127	0	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and ((eras\$4 or remov\$4 or delet\$4) with background)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:13
134	11	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:14
141	10	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4) ) and scal\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:14
148	10	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4) ) and (scale or scaling)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:15

155	10	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4) ) and (scale or scaling)) and locat\$5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:15
162	8	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4) ) and (scale or scaling)) and (locat\$5 with defect)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:28
169	3	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4) ) and (scale or scaling)) and (locat\$5 with defect)) and ((250/306,307,311,442.11)).CCLS.)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:16
176	5	((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4) ) and (scale or scaling)) and (locat\$5 with defect)) and ((superimpos\$4 or impos\$4) with imag\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:37

183	0	((((((((((((((((((((SEM or (scanning adj electron adj microscop\$3)) and (imag\$3) and defect) and (imag\$3 with defect)) and magnif\$4) and (monitor or screen)) and select\$3) and (select\$3 with area)) and display\$3) and ((mov\$3 or position\$3 or adjust\$3) with (sample or stage or wafer or mask or rectile or substrate)) ) and compar\$4) and referenc\$3) and (compar\$4 with referenc\$3)) and (superimpos\$4 or impos\$4)) and stor\$4) and calculat\$4) and data) and inspect\$5) and (eras\$4 or remov\$4 or delet\$4) ) and (scale or scaling)) and (locat\$5 with defect)) and ((superimpos\$4 or impos\$4) with imag\$4)) and ((two or second or multiple) with screen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/12 16:38
-----	---	---	---	------------------